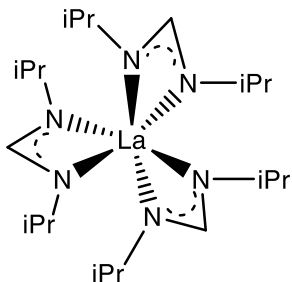


Catalog # 57-1200 Tris(N,N'-di-i-propylformamidinato)lanthanum(III), (99.999+%-La) PURATREM La-FMD



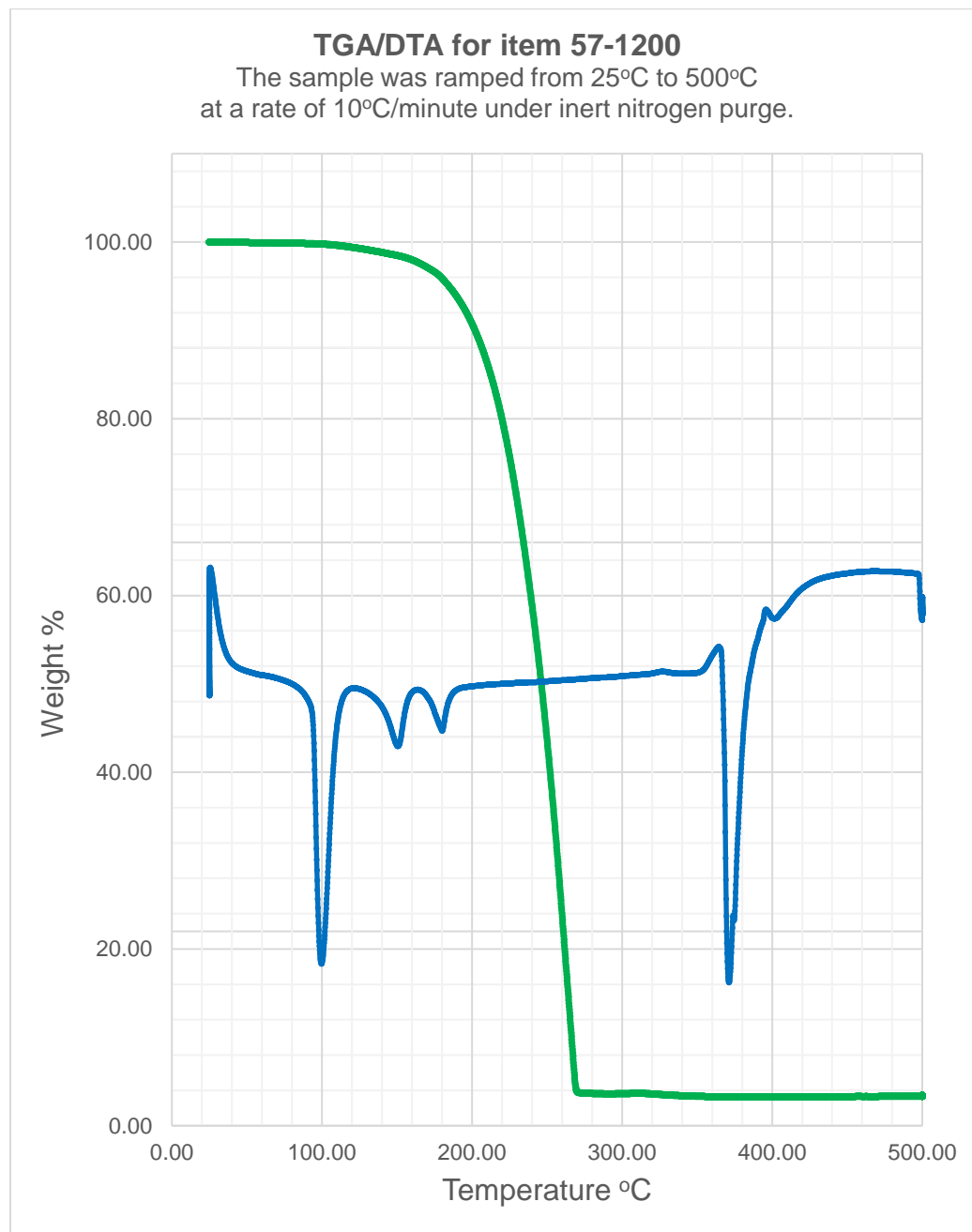
Thermal Behavior:

- Vapor pressure 82 mTorr at 120°C [1]
- TGA (see below)

Technical Notes:

1. ALD/CVD precursor for lanthanum thin film deposition.

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
LaAlO ₃	ALD	120°C	-	TMA, H ₂ O	300°C	1
	ALD	130°C	1 Torr	TMA, H ₂ O	250°C	2-3
La ₂ O ₃	ALD	120°C	-	O ₂	300°C	4
	ALD	135°C	1-3.5 Torr	O ₃	175°C	5
	ALD	150°C	0.76 Torr	O ₃	250°C	6
	ALD	-	7.6 Torr	H ₂ O	250-400°C	7



References:

1. [ECS Transactions, 2008, 16, 471.](#)
2. [ECS Trans. 2013, 54, 255.](#)
3. [J. Cryst. Growth, 2013, 363, 150.](#)
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5. [J. Electrochem. Soc. 2011, 158, H447.](#)
6. [ECS Trans. 2012, 45, 95.](#)
7. [Appl. Surf. Sci. 2014, 292, 880.](#)